

Publication No. : JP 2003-329567 A (2003.11.19)  
Inventor(s) : LUTTER STEFAN  
Assignee : NANOWORLD AG

Abstract

**PROBLEM TO BE SOLVED:** To provide a method of producing an SPM sensor being composed of a holding section 4, a cantilever 18 and a sensor tip 21 so that the sensor tip 21 projects from the surface of the cantilever 18 and is defined its boundary by three facets.

**SOLUTION:** In the producing method, a silicon wafer 1 with the crystal orientation (100) is used as a starting material, and a process of forming a pattern is chiefly carried out on the back of the wafer 1, and a process of single batch run is carried out by chiefly using a wet chemical etching process, and thereby producing the SPM sensor 22 at a low cost.